

**Amendments to the Specification:**

Please replace the paragraph beginning at line 1, page 22 with the following:

The check pattern-like common and pixel electrodes 90 and ~~[[102]]100~~ improve distortion and strength of electric fields between the common and pixel electrodes 90 and ~~[[102]]100~~ such that a faster response time is achieved. In addition, because a check pattern-like multi-domain is formed on the pixel region, a color dispersion property of the IPS-LCD device is improved. That is to say, liquid crystal molecules are differently aligned for each domain such that the different domains compensate each other to achieve a zero birefringence.

Please replace the paragraph beginning at line 7, page 22 with the following:

As previously explained, the first to seventh preferred embodiments adopt a multi-domain, where different domains compensate for each other. To achieve the multi-domain, the first to seventh preferred embodiments ~~[[uses]]~~use variously distorted electric fields such that liquid crystal molecules are differently aligned in the various domains.

Please replace the paragraph beginning at line 20, page 25 with the following:

Next, as shown in Figures 26A and 26B, the above-mentioned insulating material is deposited over the array substrate 110 such that a first passivation layer, or a second insulating layer ~~[[168]]166~~ is formed on the second metal layer. The first passivation layer ~~[[168]]166~~ is patterned to have a drain contact hole 168, which is disposed over the drain electrode 74. Then, a transparent conductive material is deposited and patterned on the first passivation layer 168 to form the pixel electrode 130 including the transverse pixel electrode 130a and perpendicular pixel electrode 130b. The transparent conductive material is preferably selected from a group consisting of indium tin oxide (ITO) and indium zinc oxide (IZO). At this point, an outermost transverse pixel electrode 130a shown in right of Figure 26B overlaps a portion of the gate line 50 with the gate-insulating layer 160 and first passivation layer 166 therebetween. The extended portion of the outermost transverse pixel electrode 130a serves as a first electrode of a storage

capacitor (reference ~~[[280]]~~180 of Figure 27B). The pixel electrode 130 has the plurality of transverse pixel electrodes 130a, the first and second perpendicular pixel electrodes 130b and 130c, and the second transverse pixel electrode 130d (see Figure 24A).

Please replace the paragraph beginning at line 4, page 26 with the following:

Next, as shown in Figures 27A and ~~[[27C]]~~27B, the insulating material is deposited and patterned over the array substrate 110 such that a second passivation layer, or a third insulating layer 170 is formed to cover the pixel electrode 130. Then, the transparent conductive material is deposited and patterned on the second passivation layer 170 to form the common electrode 120 and common line 60. The common electrode 120 includes the plurality of first transverse common electrodes 120a, first to third perpendicular common electrodes 120b to 120d, and second transverse common electrode 120e (see Figure 24A). A portion of the common line 60 serves as a second electrode of the storage capacitor 180. That is to say, portions of the outermost transverse pixel electrode 130a and common line 60 are used as the first and second electrodes for the storage capacitor 280.